

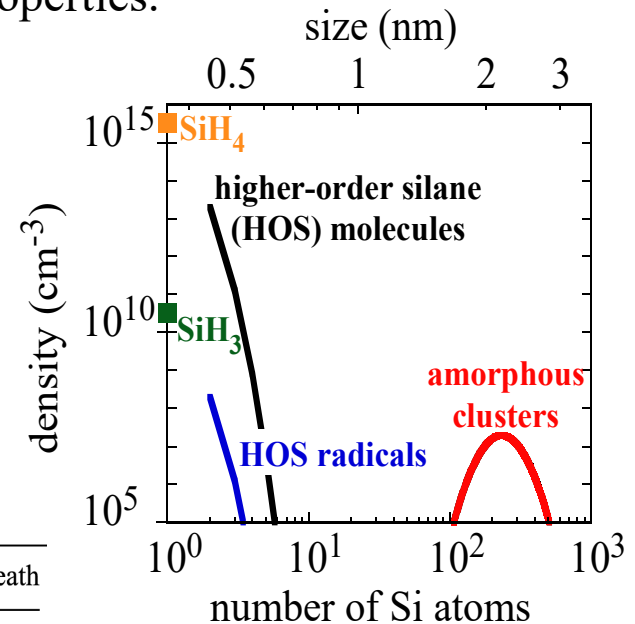
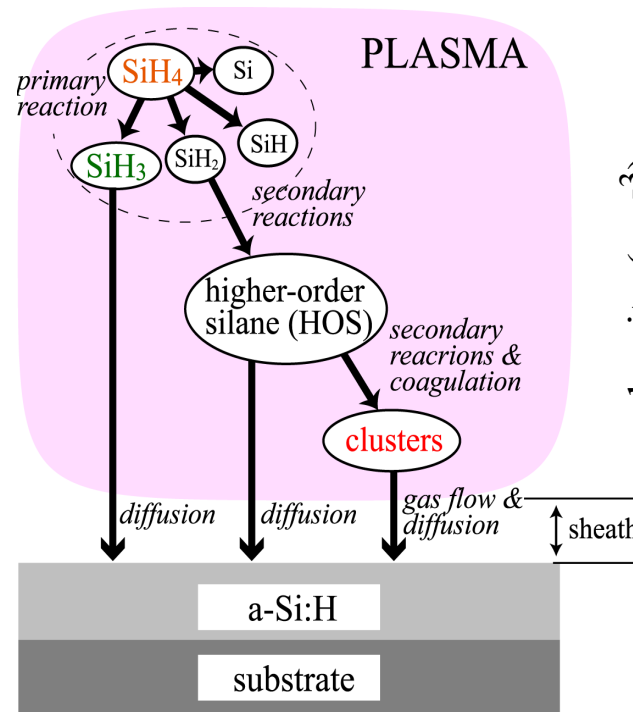
# The 3rd Plasma Materials Science Hall of Fame Prize

was awarded to

**Prof. Masaharu Shiratani,**  
Kyushu University,

for the excellent achievements in comprehensive research with regard to the measurement of higher-order radicals and fine particles in silane plasmas, clarification, and systematization of the dynamic mechanisms of gas-phase reactions, and synthesis of high-quality amorphous silicon thin films, and the tremendous contributions to the international plasma materials science community.

CVC plasma contains source gas ( $\text{SiH}_4$  for a-Si:H deposition), radicals ( $\text{SiH}_x$ ), higher order molecules ( $\text{Si}_m\text{H}_n$ ), and clusters (nano particles). Their generation, transport, and loss are the key to control film properties.



**Prof. Masaharu Shiratani**  
Kyushu University

